ABSTRACT

A positive photoresist composition comprising an alkali-soluble novolak resin

(A) containing a structural unit (a1) represented by a general formula (I) shown below, and a structural unit (a2) represented by a general formula (II) shown below, and a photosensitizer (B).

$$\begin{array}{c}
0 - R^1 - OH \\
\downarrow \qquad \qquad \downarrow \qquad \qquad \downarrow \\
R^2)_m
\end{array}$$
(1)

$$\begin{array}{c|c}
OH \\
\hline
 & H_2 \\
\hline
 & R^3)_n
\end{array}$$
(II)